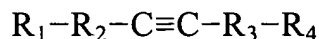


CLEANING AGENT INCLUDING A CORROSION INHIBITOR USED IN A PROCESS OF FORMING A SEMICONDUCTOR DEVICE

ABSTRACT OF THE DISCLOSURE

A cleaning solution having a corrosion inhibitor and a surfactant is disclosed. The corrosion inhibitor is represented by formula 1 and the surfactant is represented by the formula 2 as follows:

<Formula 1>



<Formula 2>



In formula 1, any one of R_1 and R_4 is a hydroxyl group (-OH) and the other is hydrogen (-H), a halogen element (-X) or one functional group selected from the group consisting of alkyl (-R) group, alkoxy (RO-) group, amino (-NH₂) group, nitro (-NO₂) group, mercapto (-SH) group, hydroxyl (-OH) group, aldehyde (-CHO) group and carboxyl (-COOH) group. R_2 and R_3 are hydrocarbons having 0 to 10 carbons including a straight or a branched structure. In formula 2, R_5 is methyl group and K is an integer ranging from 3 to 22. A is HO(CH₂CH₂O)_L(CH(CH₃)CH₂O)_M- or hydroxyl group, and L and M are integers ranging from 0 to 15.